

# ***Interactive comment on “Investigation of the $\alpha$ -pinene photooxidation by OH in the atmospheric simulation chamber SAPHIR” by Michael Rolletter et al.***

**Anonymous Referee #2**

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Rolletter and coworkers studied the photooxidation of  $\alpha$ -pinene with OH radical at atmospheric concentrations (around 4 ppb) and under low NOx conditions (<120 ppt) at the SAPHIR chamber. They compared the results with MCM and implemented additional mechanism pathways, using those proposed by Vereecken et al. to fit the experimental results with model calculations. The main adjustment arise from the production of less pinonaldehyde that could explain changes in OH, OH<sub>2</sub> and RO<sub>2</sub>

The work carried out and the data obtained is of high quality and I recommend it for publication with a very minor revision

Page 7 Line 16. How was the products production from the chamber source deter-

mined?. In previous experiments?. Do the follow a first order decay?

Page 7. Line 8. Did you use any specific instrumentation or techniques for trying to measure hydroperoxydes?

Does the calculated yield error correspond to 1 sigma?

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Interactive comment

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